

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A method of composition for forming a silicon-aluminun film, comprising:

forming a coating film comprising a silicon compound and an aluminum compound on a primer coat located on a substrate, said primer coat comprising a metal atom selected from the group consisting of Ti, Pd, and Al; and
treating the coating film with heat and /or light.

Claim 2 (Currently Amended): The method eomposition for forming a silicon-aluminum film according to claim 1, wherein the silicon compound is at least one selected from the group consisting of compounds represented by the following formulas (1) to (4):



wherein X is a hydrogen atom, halogen atom or monovalent organic group and “a” is an integer of 2 or more.



wherein X is as defined in the above formula (1) and “b” is an integer of 3 or more.



wherein X is as defined in the above formula (1) and “c” is an integer of 6 or more.



wherein X is as defined in the above formula (1).

Claim 3 (Currently Amended): The method eomposition for forming a silicon-aluminum film according to claim 1, wherein the aluminum compound is at least one

selected from the group consisting of a compound represented by the following formula (5) and a complex of an amine compound and aluminum hydride:



wherein Y is a hydrogen atom or monovalent organic group.

Claim 4 (Canceled):

Claim 5 (Currently Amended): A silicon-aluminun film formed by the method of claim 1 ~~claim 4~~.

Claim 6 (New): A silicon-aluminun film formed by the method of claim 2 ~~claim 4~~.

Claim 7 (New): A silicon-aluminun film formed by the method of claim 3 ~~claim 4~~.

Claim 8 (New): The method according to claim 2, wherein the aluminum compound is at least one selected from the group consisting of a compound represented by the following formula (5) and a complex of an amine compound and aluminum hydride:



wherein Y is a hydrogen atom or monovalent organic group.

Claim 9 (New): The method according to claim 2, wherein the silicon compounds represented by formulas (1) to (4) are at least one selected from the group consisting of halogenosilane compounds, cyclic silane compounds, chain silane compounds, silane compounds having a spiro structure, polycyclic silane compounds, and high molecular weight silane compounds obtained by the exposure of said silane compounds to light.

Claim 10 (New): The method according to claim 9, wherein the temperature for carrying out said exposure is from 25 to 300°C for a time period of from 0.1 minute to 3 hours.

Claim 11 (New): The method according to claim 3, wherein the monovalent organic group as Y in the formula (5) is at least one selected from the group of alkyl groups having 1 to 12 carbon atoms, alkenyl groups having 2 to 12 carbon atoms, alkynyl groups having 6 to 12 carbon atoms, and aryl groups having 6 to 12 carbon atoms.

Claim 12 (New): The method according to claim 1, wherein the aluminum compound is at least one complex of an amine compound and aluminum hydride wherein the amine compound is at least one selected from the group consisting of ammonia, triethylamine, phenyldimethylamine, triisobutylamine, diisobutylamine, triisopropylamine, and triphenylamine.

Claim 13 (New): The method according to claim 3, wherein the amine compound constituting the complex of an amine compound and aluminum hydride is at least one selected from the group consisting of a compounds represented by the following formula (6):



wherein R^1 , R^2 , and R^3 are each independently a hydrogen atom, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkynyl group, cyclic alkyl group and aryl group.

Claim 14 (New): The method according to claim 13, wherein the amine compound represented by formula (6) is at least one selected from the group consisting of ammonia,

triethylamine, phenyldimethylamine, triisobutylamine, diisobutylamine, triisopropylamine, and triphenylamine.

Claim 15 (New): The method according to claim 1, wherein the atomic ratio of Al to Si is from 10^{-5} to 10^{-2} .

Claim 16 (New): The method according to claim 1, wherein the atomic ratio of Al to Si is from 0.3 to 30.

Claim 17 (New): The method according to claim 1, wherein the silicon-aluminum film further comprises at least one metal or semiconductor particle selected from the group consisting of gold, silver, copper, aluminum, nickel, iron, niobium, titanium, silicon, indium and tin.

Claim 18 (New): The method according to claim 1, wherein the silicon-aluminum film further comprises at least one metal oxide selected from the group consisting of aluminum oxide, zirconium oxide, titanium oxide, and silicon oxide.

Claim 19 (New): The method according to claim 1, wherein the silicon-aluminum film further comprises at least one surfactant selected from the group consisting of fluorine-based surfactant, silicone-based surfactant, and nonionic surfactant.

Claim 20 (New): The method according to claim 1, wherein the method for forming the silicon-aluminum film further comprises applying a protective film to the silicon-aluminum film.

Claim 21 (New): The method according to claim 1, wherein the primer coat is formed by pre-coating the substrate with a solution comprising an organic metal compound wherein the organic metal compound comprises a metal atom selected from the group consisting of Ti, Pd, and Al.